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Application Number	To Be Assigned
Filing Date	November 28, 2001
First Named Inventor	Hatakeyama, et al.
Group Art Unit	To Be Assigned
Examiner Name	To Be Assigned
Attorney Docket Number	KOJIM-436

U.S. PATENT DOCUMENTS

Examiner Initials *	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
S.J.L. ↓	A	4,491,628		Ito et al.	01/01/85	
	B	5,310,619		Crivello et al.	05/10/94	
	C	5,580,695		Murata et al.	12/03/96	
	D	5,609,989		Bantu et al.	05/11/97	

FOREIGN PATENT DOCUMENTS

Examiner Initials *	Cite No. ¹	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ₆
		Office ³	Number ⁴	Kind Code ⁵ (if known)				
S.J.L. ↓	E	JP	63027829	A	Crivello et al.	05/02/88		
	F	JP	90027660	B	Frechet et al.	06/19/90		
	G	WO	9837458	A1	Sone et al.	08/27/98		
	H	JP	63149640	A		06/22/98		
	I	JP	5113666	A		05/07/93		
	J	JP	5232706	A	Kobayashi et al.	09/10/93		
	K	JP	5249683	A	Kobayashi et al.	09/28/93		
	L							
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OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials *	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
S.J.L. ↓	N	HATAKEYAMA, et al., "Investigation of Discrimination Enhancement with New Modeling for Poly-hydroxystyrene Positive Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 13, No. 4 (2000) pp 519-524	
	O	HINSBERG et al., "Fundamental Studies of Airborne Chemical Contamination of Chemically Amplified Resists," <i>Journal of Photopolymer Science and Technology</i> , Vol. 6, No. 4 (1993) pp 535-546.	
	P	KUMADA, et al., "Study on Over-Top Coating of Positive Chemical Amplification Resists for KrF Excimer Laser Lithography," <i>Journal of Photopolymer Science and Technology</i> , Vol. 6, No. 4 (1993) pp 571-574.	

Examiner Signature

Si J. Lee

Date Considered

9-4-2003

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